

## REMARKS

Claims 1-18 are pending in this application.

Claims 1, 7, 9, 13, 14 and 18 have been amended. It is respectfully submitted that no new matter has been added.

### REJECTIONS UNDER 35 U.S.C. § 103:

Claims 1-18 stand rejected under 35 U.S.C. 103(a) as being unpatentable over Pierrat (US 5,935,734) in view of Kawashima (US 6,991,896).

Amended claim 1 recites, *inter alia*, at least one through hole located to evenly divide a first longitudinal pitch of the light-shielding pattern, wherein the first longitudinal pitch is the distance from one center point between a pair of light shielding patterns to another center point between a neighboring pair of light shielding patterns in a longitudinal axis. Amended claims 9 and 14 recite, *inter alia*, a step of forming at least one through hole comprising locating the at least one through hole to evenly divide a first longitudinal pitch of the light-shielding pattern, wherein the first longitudinal pitch is the distance from one center point between a pair of light shielding patterns to another center point between a neighboring pair of light shielding patterns in a longitudinal axis.

Applicants respectfully submit that neither Pierrat, Kawashima, nor any combinations thereof discloses or suggests at least one through hole located to evenly divide a first longitudinal pitch of the light-shielding pattern, as essentially recited in amended claims 1, 9 and 14.

The Examiner acknowledges that Pierrat does not disclose at least one through hole having a size smaller than a distance between the light-shielding patterns. It follows that Pierrat does not disclose at least one through hole located to evenly divide a first

longitudinal pitch of the light-shielding pattern. For this element, the Examiner relies on Kawashima.

Applicants respectfully submit that Kawashima does not disclose or suggest at least one through hole located to evenly divide a first longitudinal pitch of the light-shielding pattern. Kawashima is directed to an exposure method including the step of providing a mask that arranges a contact-hole pattern. However, Kawashima is completely silent on a relative location of a contact hole with respect to a longitudinal pitch of the light-shielding pattern.

Accordingly, even assuming, *arguendo*, that Pierrat and Kawashima were combined, the combination does not disclose or suggest at least one through hole located to evenly divide a first longitudinal pitch of the light-shielding pattern.

Since claims 2-8, 10-13 and 15-18 depend from claims 1, 9 and 14, respectively, these dependent claims are also patentable for the same reasons given above for claims 1, 9 and 14.

Therefore, Applicants respectfully request that Examiner withdraw the rejection of claims 1-18 under 35 U.S.C. § 103(a) and that claims 1-18 are in condition for allowance.

An early and favorable reconsideration is earnestly solicited. If the Examiner has any further questions or comments, the Examiner may telephone Applicants' Attorney to reach a prompt disposition of this application.

Respectfully submitted,

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